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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/607,156	156 06/26/2003		Keun-Deok Park	5000-1-321	5603	
33942	7590	09/01/2005		EXAMINER		
CHA & RE	•		METZMAIER, DANIEL S			
210 ROUTE PARAMUS.			ART UNIT	PAPER NUMBER		
				1712	1712	
				DATE MAIL ED: 00/01/2006	DATE MAIL ED: 00/01/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	10/607,156	PARK ET AL.					
Office Action Summary	Examiner	Art Unit					
	Daniel S. Metzmaier	1712					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA: - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w. - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be time will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONEI	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).					
Status							
1) Responsive to communication(s) filed on 01 Au	<u>ugust 2005</u> .						
· <u>-</u>	This action is FINAL. 2b)⊠ This action is non-final.						
• • • • • • • • • • • • • • • • • • • •	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.							
Disposition of Claims							
4)⊠ Claim(s) <u>1-17</u> is/are pending in the application.							
4a) Of the above claim(s) 1-4,9 and 11-14 is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6) Claim(s) <u>5-8,10 and 15-17</u> is/are rejected.							
7) Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction and/or election requirement.							
Application Papers							
9) The specification is objected to by the Examine	r.						
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
Applicant may not request that any objection to the							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).							
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No							
3. Copies of the certified copies of the priority documents have been received in this National Stage							
application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.							
See the attached detailed Office action for a list of	on the certified cobies not receive	d.					
Attachment(s)							
1) Notice of References Cited (PTO-892)	4) Interview Summary						
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) 	Paper No(s)/Mail Da 5) Notice of Informal Pa	ate Patent Application (PTO-152)					
Paper No(s)/Mail Date	6) Other:	,					

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DETAILED ACTION

Claims 1-17 are pending. Claims 1-4, 9, and 11-14 have been withdrawn from consideration. Claims 5-8, 10 and 15-17 have been treated on the merits.

Election/Restrictions

1. Applicant's election of Group II, claims 5-8, 10, and 15-17, in the reply filed on August 1, 2005 and July 14, 2005 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Priority

2. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Claim Rejections - 35 USC § 112

- 3. The following is a quotation of the second paragraph of 35 U.S.C. 112:
 The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter, which the applicant regards as his invention.
- 4. Claims 10 and 16 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. Claim 10 lacks antecedent basis for "applying a third heat treatment to remove organic materials". A "third heat treatment" suggest a first and second heat treatment, which is not set forth in claim 5.

In claim 16, the basis of the 45% is unspecified and thus indefinite.

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Claim Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 8. Claims 5-6, 8, and 10 are rejected under 35 U.S.C. 102(b) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Szekeres et al, "Adsorption of dodecyl pyridinium chloride on monodisperse porous silica", *Colloids and Surfaces A:*Physicochemical and Engineering Aspects 141 (1998) 327-336. Szekeres et al (page

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329, 2.2 Preparation of monodisperse silica) discloses the formation of silica colloids according to the Stöber method employing tetraethylorthosilicate (synonymous with tetraethoxysilane), ethanol, and ammonia solution (implicitly an aqueous solution). Szekeres et al (page 329) discloses the silica was centrifuged and redispersed in water and said washing procedure was repeated several times. Szekeres et al (page 330, 2.3 Other Materials) discloses the water was deionized water. Any variation in less aqueous phase employed to re-disperse the silica reads on the claimed concentrating step.

To the extent the Szekeres et al reference <u>differs</u> in an explicit disclosure of the concentrating step, the re-dispersion in less water than the original silica colloidal solution clearly reads on the step of concentration and would have been obvious form of washing within the skill of one having ordinary skill in the art at the time of applicants' invention for the advantage of storage space and cost-effectiveness.

9. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Szekeres et al, "Adsorption of dodecyl pyridinium chloride on monodisperse porous silica", *Colloids and Surfaces A: Physicochemical and Engineering Aspects* 141 (1998) 327-336, in view of Romberger et al, US 5,230,833. Szekeres et al discloses methods as set forth in the preceding rejection.

Szekeres et al <u>differs</u> from claim 7 in the use of the analogous compound tetramethyl-ammonium hydroxide rather than tetraethyl-ammonium hydroxide.

Romberger et al (column 5, lines 64, to column 6, line 10) discloses the use of hydrolysis/condensation of tetramethyl- or tetraethyl-orthosilicate to form low metal

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colloidal silicas. Romberger et al (column 6, lines 6-8) discloses the use of tetra<u>m</u>ethylammonium hydroxide, tetraethyl-ammonium hydroxide, or mixtures thereof. Romberger et al (column 9, lines 54 et seq) further teach the tetraalkyl-ammonium hydroxides provide bactericidal activity in silica compositions.

These references are combinable since they teach hydrolysis/condensation of tetramethyl- or tetraethyl-orthosilicate to form low metal colloidal silicas stabilized by tetraalkyl-ammonium hydroxides. It would have been obvious to one of ordinary skilled in the art at the time of applicants' invention to employ tetraethyl-ammonium hydroxide for the tetramethyl-ammonium hydroxide employed in the Szekeres et al methods as an obvious functional equivalent thereto as shown in the Romberger et al reference.

10. Claims 7 and 15-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Korea Advanced Institute of Science and Technology, KR 2001019612 A (hereafter KR '612), as evidenced by So et al, US 6,432,151, and Derwent Abstract AN 2001-600594, collectively in view of Szekeres et al, "Adsorption of dodecyl pyridinium chloride on monodisperse porous silica", *Colloids and Surfaces A: Physicochemical and Engineering Aspects* 141 (1998) 327-336, and Wolter, US 2,601,352.

KR '612 is a family member of So et al as shown by Derwent AN 2001-600594. So et al is evidence as an English language translation of the KR '612 reference. The references are deemed to be the same or substantially the same as family member documents based on the same priority application, i.e., KR-99-36126. The citations refer to the corresponding disclosure in the So et al reference.

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KR '612 and So et al (column 4, lines 36 et seq; and column 5, lines 31 et seq) disclose making silica colloid composition by mixing and agitating tetraethylorthosilicate (TEOS), ethanol, water and ammonium hydroxide. KR '612 and So et al (column 5, lines 31 et seq) teach maintaining pH of about 11 to 11.5 for electrostatic repulsion (e.g., stability) and displacing the ethanol with aqueous phase by vacuum distillation and an ultracentrifuge. KR '612 and So et al (column 6, lines 55 et seq; and examples) disclose the addition of tetramethyl-ammonium hydroxide (TMAH) as a polishing aid.

KR '612 and So et al <u>differ</u> from the claims in an explicit disclosure of the concentrating step, the pH range of more than 12 or 12 to 12.8, and the concentration of 45% or more.

Szekeres et al (page 329) discloses related processes wherein silica was centrifuged and redispersed in water and said washing procedure was repeated several times. Szekeres et al (page 330, 2.3 Other Materials) discloses the water was deionized water. Any variation in less aqueous phase employed to re-disperse the silica reads on the claimed concentrating step.

Wolter (column 7, lines 1-15) discloses the stabilization of silica sols employing among other quaternary ammonium hydroxides, the use of tetramethyl-ammonium hydroxide, tetraethyl-ammonium hydroxide, or mixtures thereof. Wolter (column 3, lines 9 et seq) further teach the tetraalkyl-ammonium hydroxides provide products having unusually high silica concentrations of 70% SiO₂ or more in the silica compositions.

These references are combinable since they teach hydrolysis/condensation of tetramethyl- or tetraethyl-orthosilicate to form low metal colloidal silicas stabilized by tetraalkyl-ammonium hydroxides.

It would have been obvious to one of ordinary skilled in the art at the time of applicants' invention to employ the re-dispersion in less water than the original silica colloidal solution as an obvious form of washing within the skill of one having ordinary skill in the art at the time of applicants' invention for the advantage of storage space and cost-effectiveness. Applicants have not shown the concentration of 45% or more to be critical to applicants invention.

It would have been obvious to one of ordinary skilled in the art at the time of applicants' invention to employ tetraethyl-ammonium hydroxide for the tetramethyl-ammonium hydroxide employed in the KR '612 and So et al methods as an obvious functional equivalent thereto as shown in the Romberger et al reference.

Conclusion

11. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daniel S. Metzmaier whose telephone number is (571) 272-1089. The examiner can normally be reached on 9:00 AM to 5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Randy P. Gulakowski can be reached on (571) 272-1302. The fax phone

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number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

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Daniel S. Metzmaier C Primary Examiner Art Unit 1712

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